WEST Search History

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DATE: Thursday, March 29, 2007

Hide?	Set Name	Query	Hit Count
		DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ	
☐	L8	L7 and l6	32
☐	L7	134/1.2,21,26,30,31,25.4,42,36;216/55,67;438/710,715,906.ccls.	12120
☐	L6	($5resist or polymer) same (bak$3 or anneal$3) same (ash$3 or strip$4 or clean$3 or remov$3) same plasma same (pressur$5 or vacuum$5 or ambient or normal) same (heat$3 or temperature)	450
		DB=EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ	
☐	L5	($5resist or polymer) same (bak$3 or anneal$3) same (ash$3 or strip$4 or clean$3 or remov$3) same plasma same (pressur$5 or vacuum$5 or ambient or normal) same (heat$3 or temperature)	30
		DB=EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ	
☐	L4	($5resist or polymer) same (bak$3 or anneal$3) same (ash$3 or strip$4 or clean$3 or remov$3) same plasma same (pressur$5 or vacuum$5) same (heat$3 or temperature)	15
☐	L3	($5resist or polymer) same (bak$3 or anneal$3) same ((ash$3 or strip$4 or clean$3) with plasma) same (pressur$5 or vacuum$5) same (heat$3 or temperature)	3
☐	L2	($5resist or polymer) same (bak$3 or anneal$3) same ((ash$3 or strip$4 or clean$3) with plasma)	62
		DB=USPT; PLUR=YES; OP=ADJ	
☐	L1	5968379.pn. or 5993916.pn. or 6130169.pn. or 6200911.pn.	4

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DATE: Thursday, March 29, 2007

Hide?	Set Name	Query	Hit Count
		DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ	
☐	L8	L7 and ((semiconductor or wafer or substrate) same (bak$3 or anneal$3) same (vacuum or pressure) same (ash$3 or strip$4 or clean$3))	2
☐	L7	L6 or l5 or l4 or l3 or l2	1566
☐	L6	(psk).as.	18
☐	L5	Yang-seung$.in.	281
☐	L4	park-jin$.in.	994
☐	L3	song-yong$.in.	165
☐	L2	jeon-jong$.in.	120
		DB=USPT; PLUR=YES; OP=ADJ	
☐	L1	jeon-jong$.in.	29

END OF SEARCH HISTORY